







大直径LEC Si-GaAs中深施主缺陷的红外光谱分析*

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摘 要:本文利用红外光谱分析技术系统分析大直径LEC(Light Energy Converter 光能转换器) Si-GaAs 中深施主缺陷EL2的浓度分布。实验结果表明,大直径LEC Si-GaAs深施主缺陷EL2浓度沿直径方向成W型分布,中心区域比较高,靠近中间区域最低,边缘区域最高。EL2是GaAs晶体中过量As存在的一种形式,其浓度强烈依赖过量As的浓度。晶体生长后的冷却过程中热应变场对过量As的分布会造成一定影响,同时位错密度的分布也会影响过量砷的分布,也就影响深施主缺陷EL2浓度的分布。

关键词: 半绝缘砷化镓, EL2, 红外光谱分析

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Infrared spectroscopy analysis of deep donor defect in large diameter LEC Si-GaAs

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Abstract: In this paper, the concentration distribution of deep donor defect EL2 in large diameter LEC Si-GaAs has been analysed by Infrared Spectroscopy analysis. The results shows that the distribution of deep donor defect EL2 concentration are W-shape along the diameter. As a existent form of excessive As in GaAs crystal, the concentration of EL2 strongly dependents on the concentration of excess As, which can be affected to a certain degree by the hot strain field in the cooling process of Crystal Growth. At the same time, the distribution of dislocation density will affect the distribution of excess arsenic, so that the distribution of EL2 also can be impacted by the distribution of dislocation density. Key words: Si-GaAs, EL2, Infrared spectroscopy analysis

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